

ISO 16531:2013-06 (E)

Surface chemical analysis - Depth profiling - Methods for ion beam alignment and the associated measurement of current or current density for depth profiling in AES and XPS

Contents		Page
Foreword		iv
Introduction		v
1	Scope	1
2	Normative references	1
3	Terms, definitions, symbols and abbreviated terms	1
4	System requirements	2
4.1	General	2
4.2	Limitations	2
5	Ion beam alignment methods	3
5.1	General	3
5.2	Important issues to be considered prior to ion beam alignment	3
5.3	Alignment using circular-aperture Faraday cup	6
5.4	Alignment using elliptical-aperture Faraday cup	9
5.5	Alignment using images from ion-induced secondary electrons during ion beam rastering	9
5.6	Alignment in X-ray photoelectron microscope/photoelectron imaging system	11
5.7	Alignment by observing direct ion beam spot or crater image during and/or after ion sputtering	12
5.8	Alignment by observing phosphor sample	13
6	When to align and check ion beam alignment	13
	Annex A (informative) Comparison of AES depth profiles with good/poor ion beam alignment	14
	Annex B (informative) Alignment using cup with co-axial electrodes	16
	Bibliography	18